Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-584002	Application No.	
Information Disclosure Statement by Applicant		Applicant Chris E. Barns et al.		
(Use several she	eets if necessary)	Filing Date March 12, 2004	Group Art Unit	

	U.S. Patent Documents								
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate		
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Foreign Patent Documents or Published Foreign Patent Application								
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N. di f. D. farancas Citad	Application/Control No.	Applicant(s)/Patent Under Reexamination BARNS ET AL.		
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